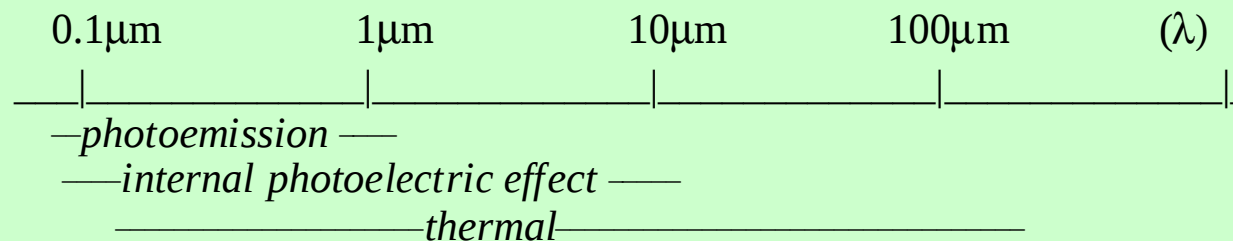


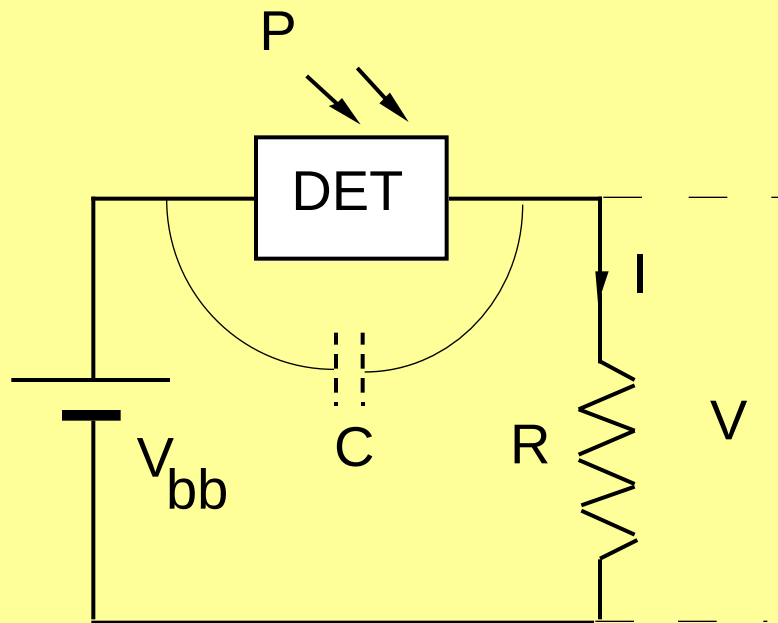
Photodetectors and their Spectral Ranges

	SINGLE ELEMENT	IMAGE
- <i>photoemission devices</i> (or external <i>photoelectric devices</i>)	vacuum photodiode gas photodiode photomultiplier	pickup tubes image intensifiers and converters
- <i>internal photoelectric devices</i>	semiconductor photodiode avalanche photodiode phototransistor (BJT, FET) photoresistance	CCDs vidicon
- <i>thermal detectors</i>	thermocouple (or photopile) thermistor (or bolometer) pyroelectric	uncooled IR FPA IR vidicon
- <i>weak interaction detectors</i>	photon drag, Golay cell photoelectromagnetic point contact diode	



from: "Photodetectors", by S. Donati, Prentice Hall 2000

Detectors based on Photoelectric effect



Power collected $P = h\nu F$

is a flux F of photons of energy $h\nu$

Output current $I = e F'$

is a flux F' of electrons of charge e

Then, current is proportional to power,

$$I/P = \sigma = e F' / h\nu F = \eta (e / h\nu)$$

where $\eta = F'/F$ is **quantum efficiency** (electrons-to-photons)

and $\sigma = I/P = \eta (\lambda e / hc) = \eta (\lambda / 1.24) \text{ [A/W]}$

is **spectral sensitivity** (current out -to-power in)

Detectors based on Photoelectric effect 2

To trade photons for electrons we need a material requiring an energy not larger than the photon energy, so $h\nu \geq E_{cc}$, where energy E_{cc} for the charge carrier generation is E_W (work function) in external and E_G (bandgap) in internal photoemission.

This is the threshold condition: $hc/\lambda \geq E_{cc}$ or

$$\lambda \leq \lambda_t = hc/eE_{cc} = 1.24 / E_{cc} (eV)$$

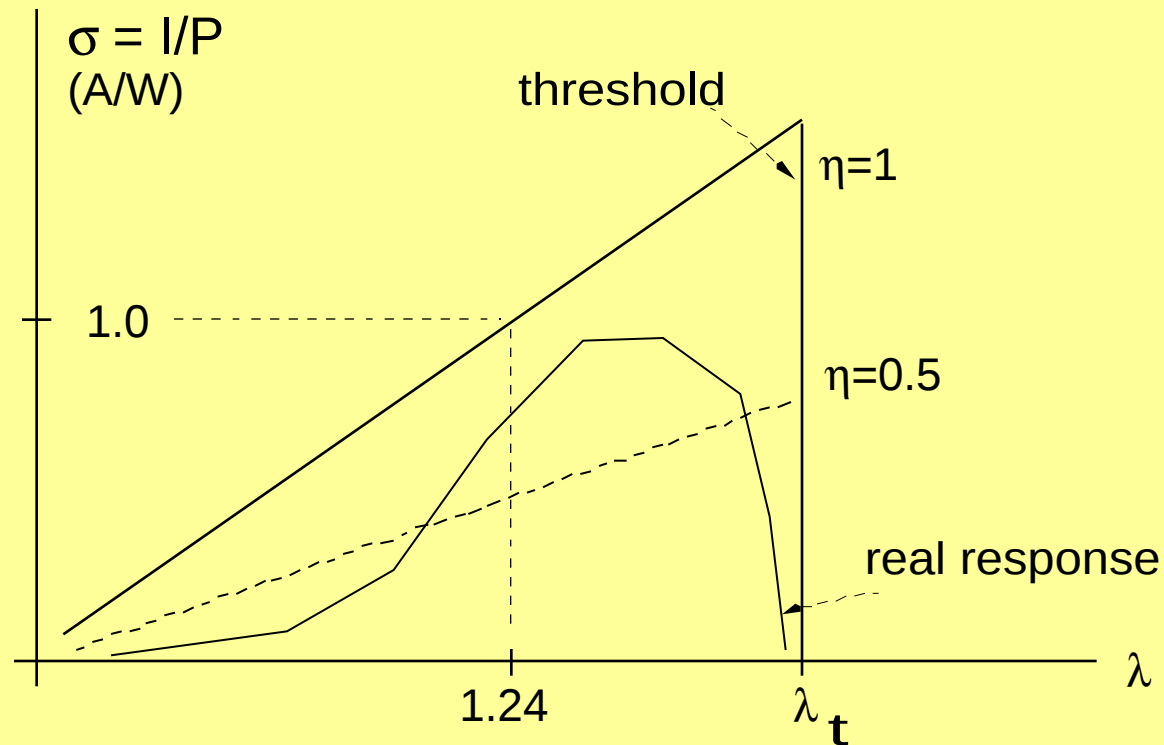
In alkaline antimonides, $E_W \approx 1.2-3.0$ eV,
and $\lambda_t \approx 1-0.4$ μm (blue to NIR)

ternaries (InGaAs) $E_G \approx 0.75$ eV, $\lambda_t \approx 1.8$ μm

InSb $E_G \approx 0.25$ eV, $\lambda_t \approx 5$ μm (MIR)

HgCdTe $E_G \approx 0.08$ eV, $\lambda_t \approx 16$ μm (FIR)

Detectors based on Photoelectric effect 3



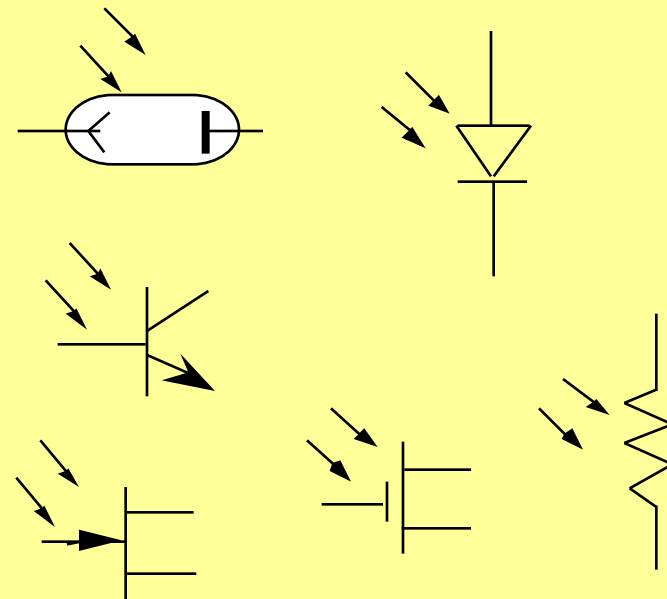
general response curve of a quantum detector:
at $P=\text{cons}$, current increases linearly with λ , then
sharply decreases to 0 at the photoelectric threshold
a real detector has a curve rather than a triangle

Detectors based on Photoelectric effect 4

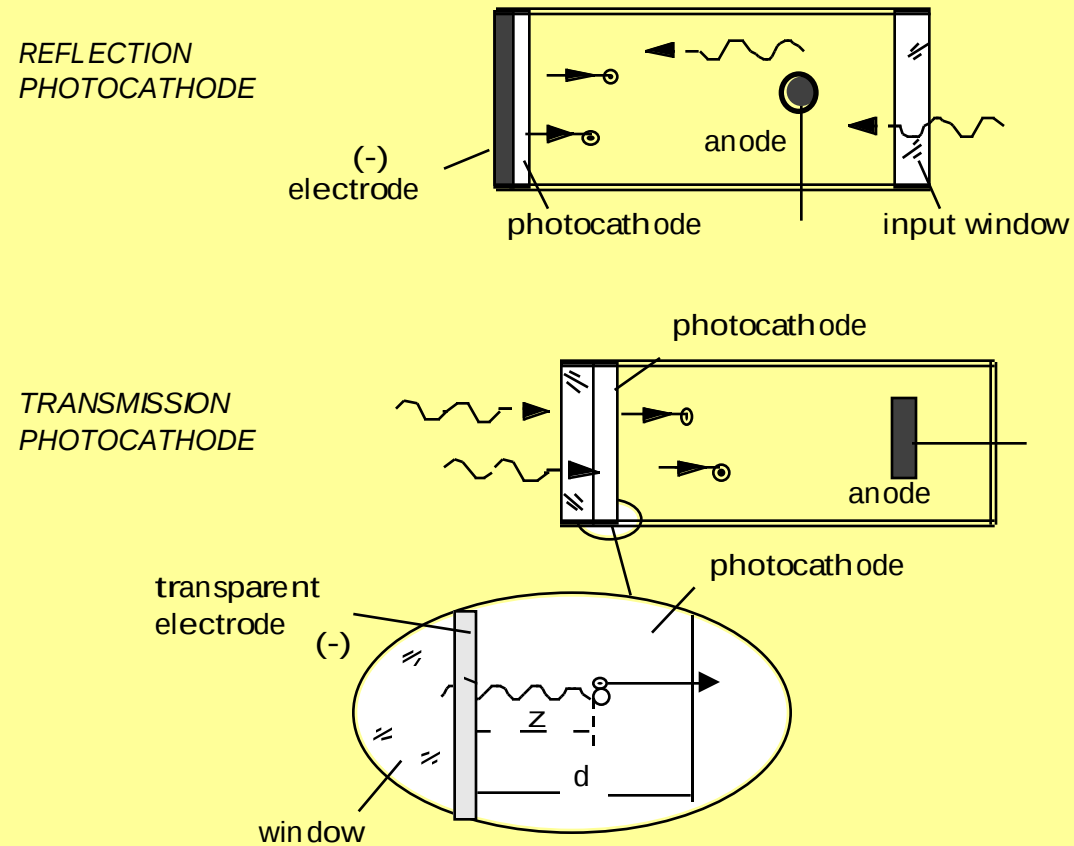
Once produced, we shall remove charge carriers fast, so we need very thin layers to cross or a favorable electric field helping collection

pn junction in a diode
base-collector junct.of BJT
gate-drain junct in a FET
depleted layer in a MOS
3rd junct in a SCR
applied field in a resistance

photocathodes

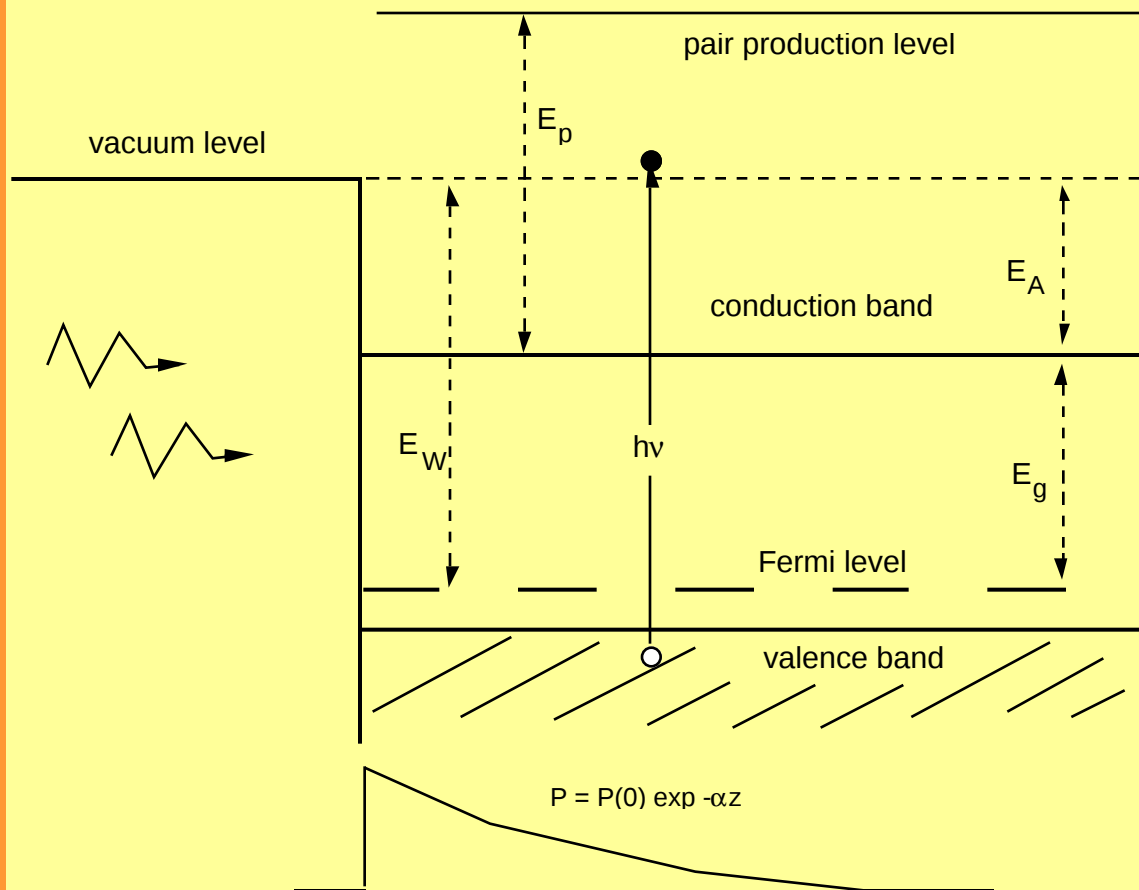


TYPES OF PHOTOCATHODES



PHOTOEMISSION PROCESS

- i) photon absorption and generation of an electron-hole pair
- ii) diffusion of the electron to the surface
- iii) emission of the electron in the vacuum



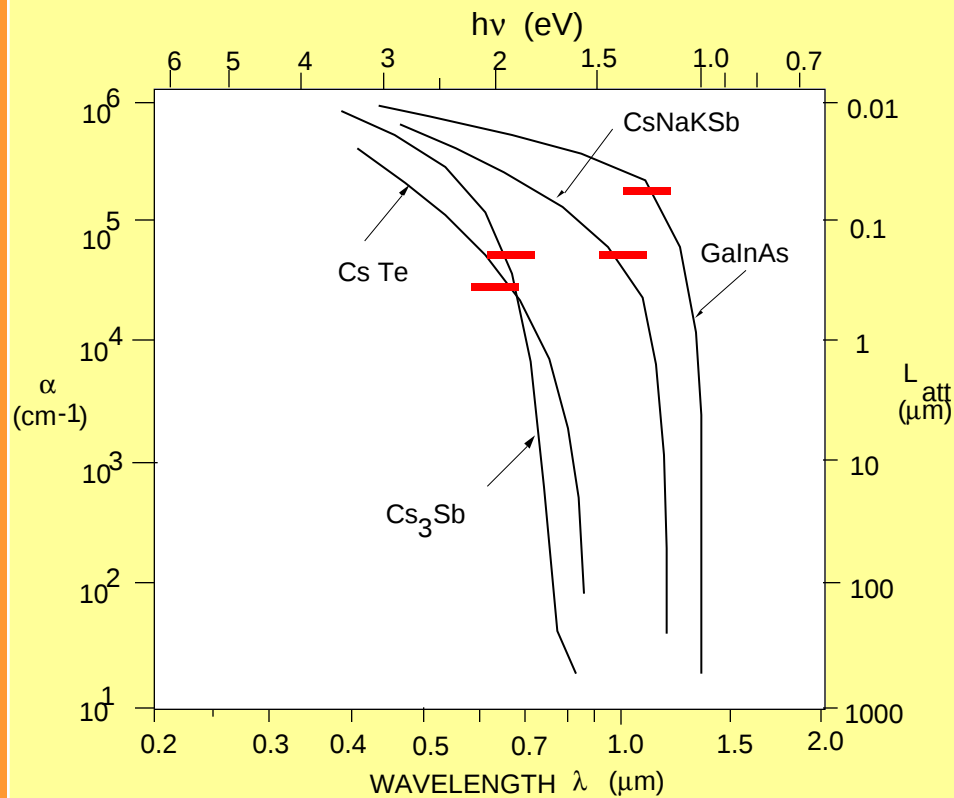
$$h\nu \geq E_g + E_A$$

$$\lambda_t = hc / (E_g + E_A)$$

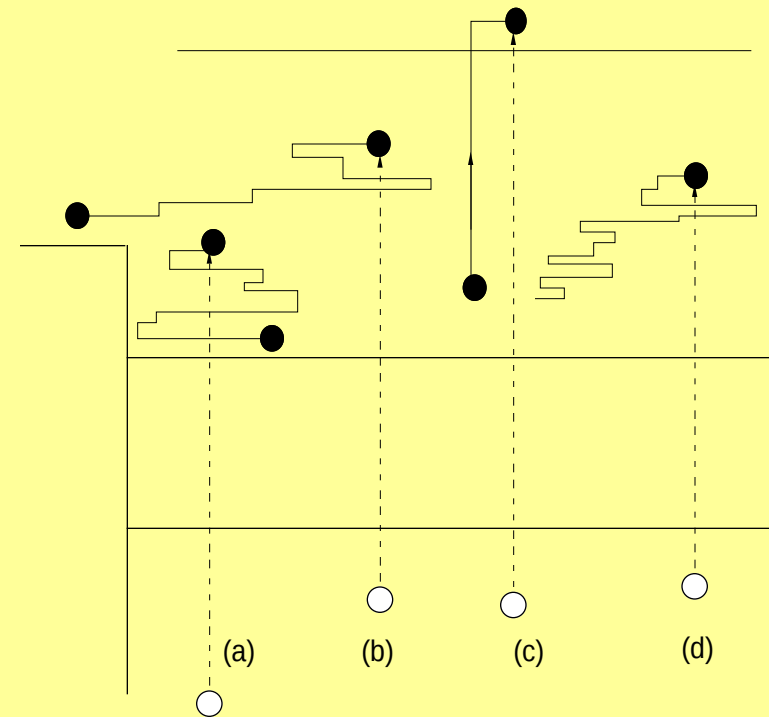
$$\lambda_{t [\mu m]} = 1.24 / E_{[eV]}$$

$$E_p \gg E_A$$

ABSORPTION and DIFFUSION

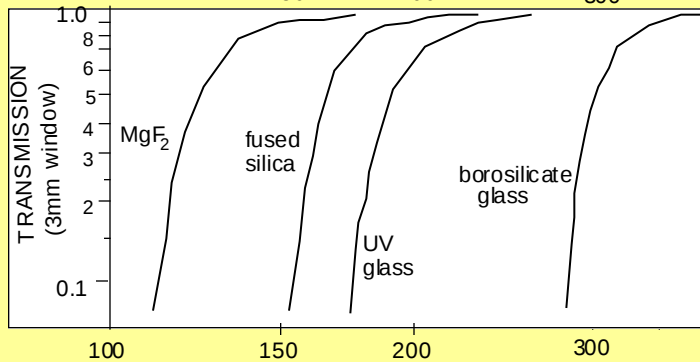
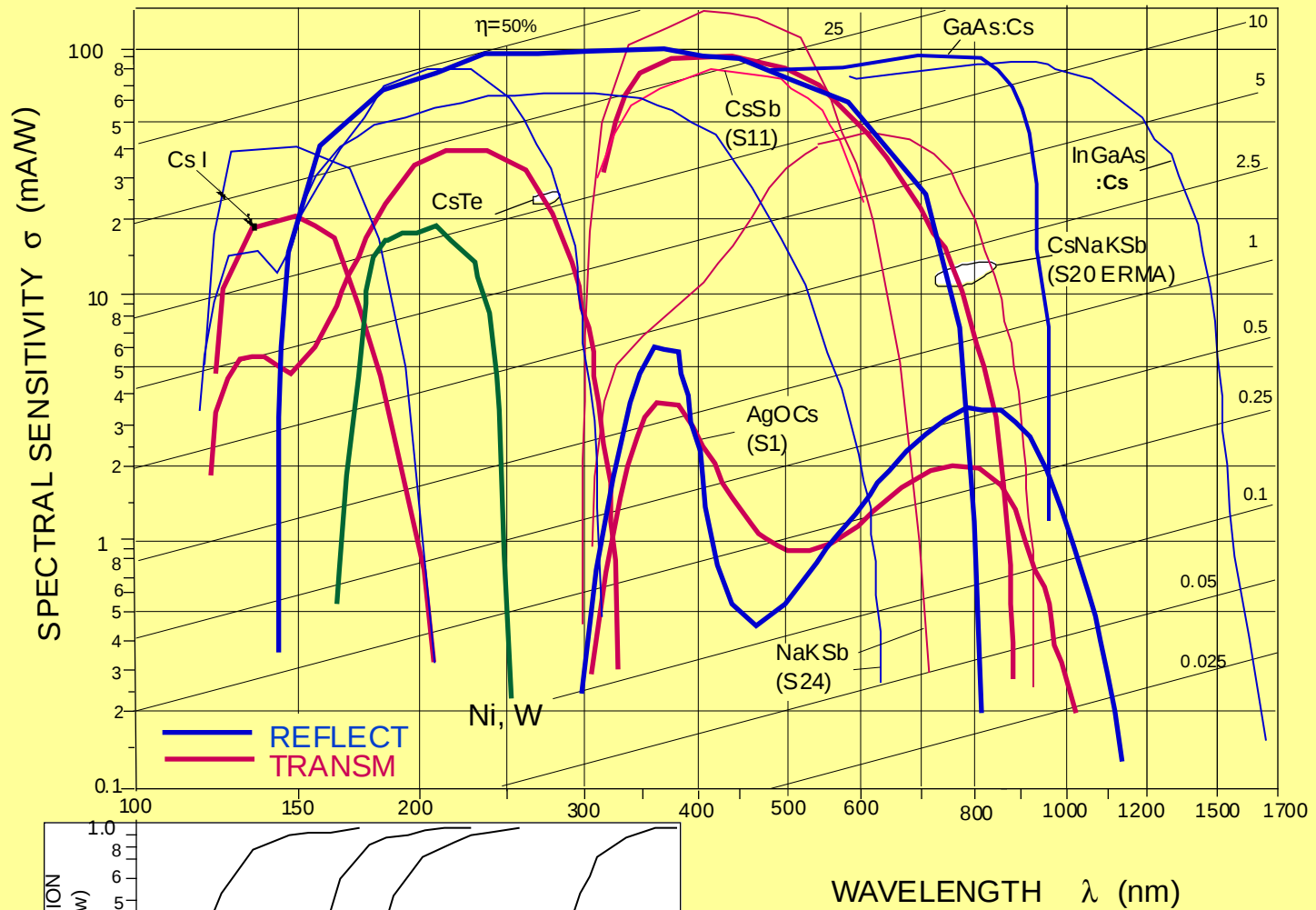


absorption



diffusion to the surface

Photocathode responses



EFFICIENCY CALCULATION

$$p(L) = (1/\Lambda) \exp -L/\Lambda ; \quad p(\theta) = 1/2\pi$$

$$p(z) = \text{gauss}(z, \Lambda) = [1/\sqrt{(2\pi)\Lambda}] \exp -z^2/2\Lambda^2$$

$$\langle l \rangle = l_f \sqrt{(\Delta E / \Delta e_f)}$$

$$p_1(E, z) = p(E - \Delta e) \text{ gauss}(z, \Lambda)$$

$$p_2(E, z) = p(E - k\Delta e) \text{ gauss}(z, \sqrt{2}\Lambda)$$

.....

$$p_k(E, z) = p(E - k\Delta e) \text{ gauss}(z, \sqrt{k}\Lambda)$$

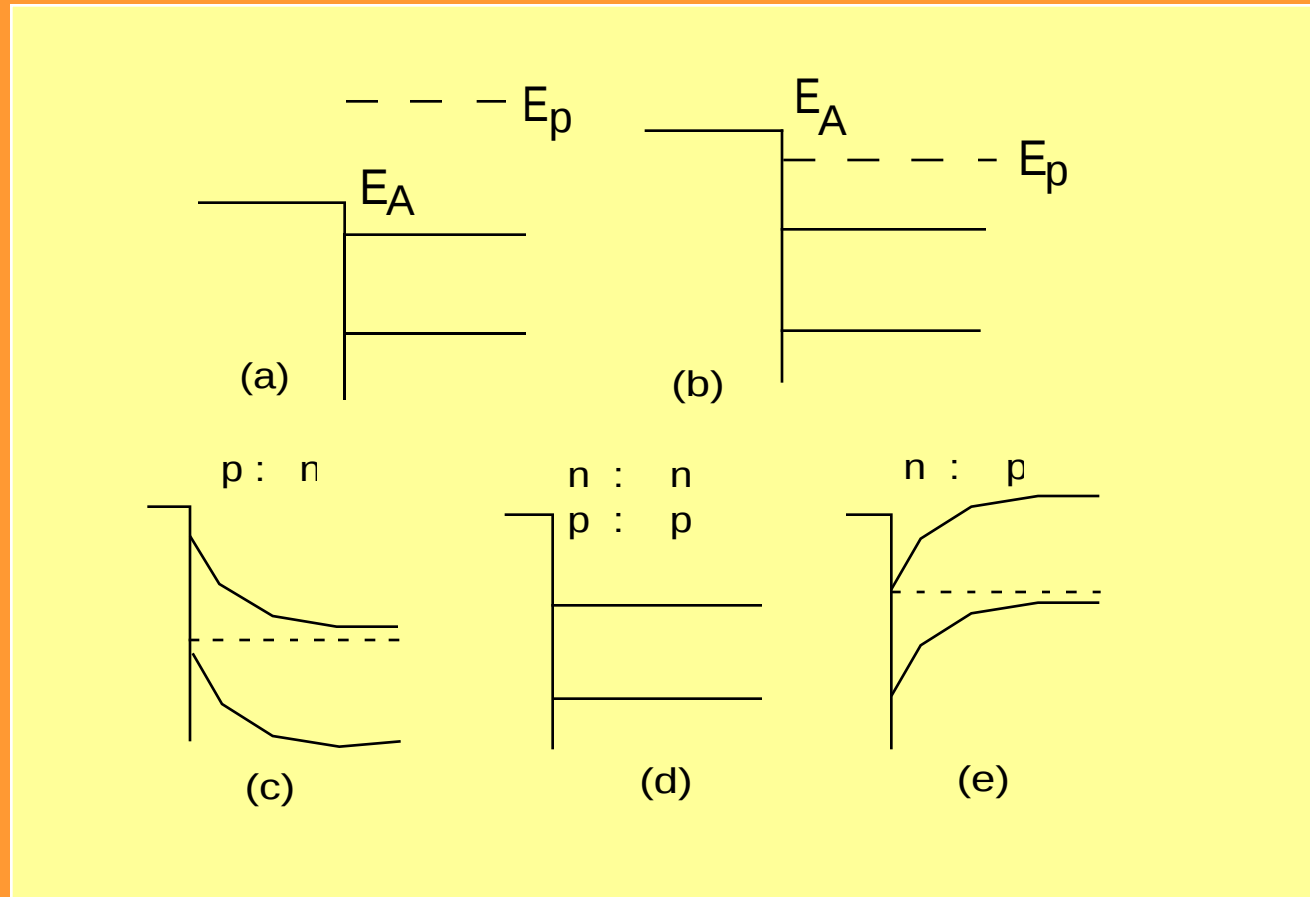
$\Pi(z)$ = escape probability

$$\eta_e = \int_{0-\infty} \Pi(z) \propto \exp -\alpha z \, dz,$$

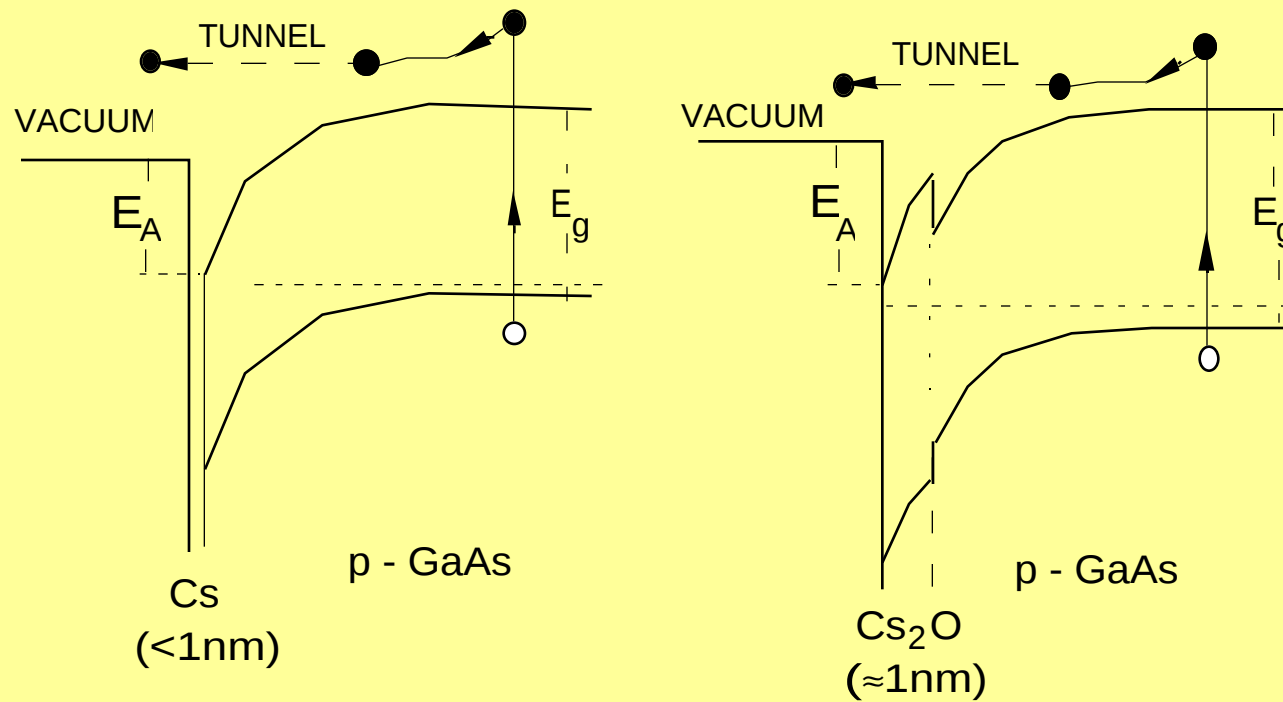
$$\Pi(z) = \int_{EA-\infty} dE \int_{z-\infty} [\sum_{k=0-\infty} p_k(E, z')] \, dz' \quad \text{(reflection photocathode)}$$

$$\Pi(d-z) = \int_{EA-\infty} dE \int_{(d-z)-\infty} [\sum_{k=0-\infty} p_k(E, z')] \, dz' \quad \text{(transmission photocathode)}$$

BAND BENDING AT THE SURFACE



NEGATIVE AFFINITY

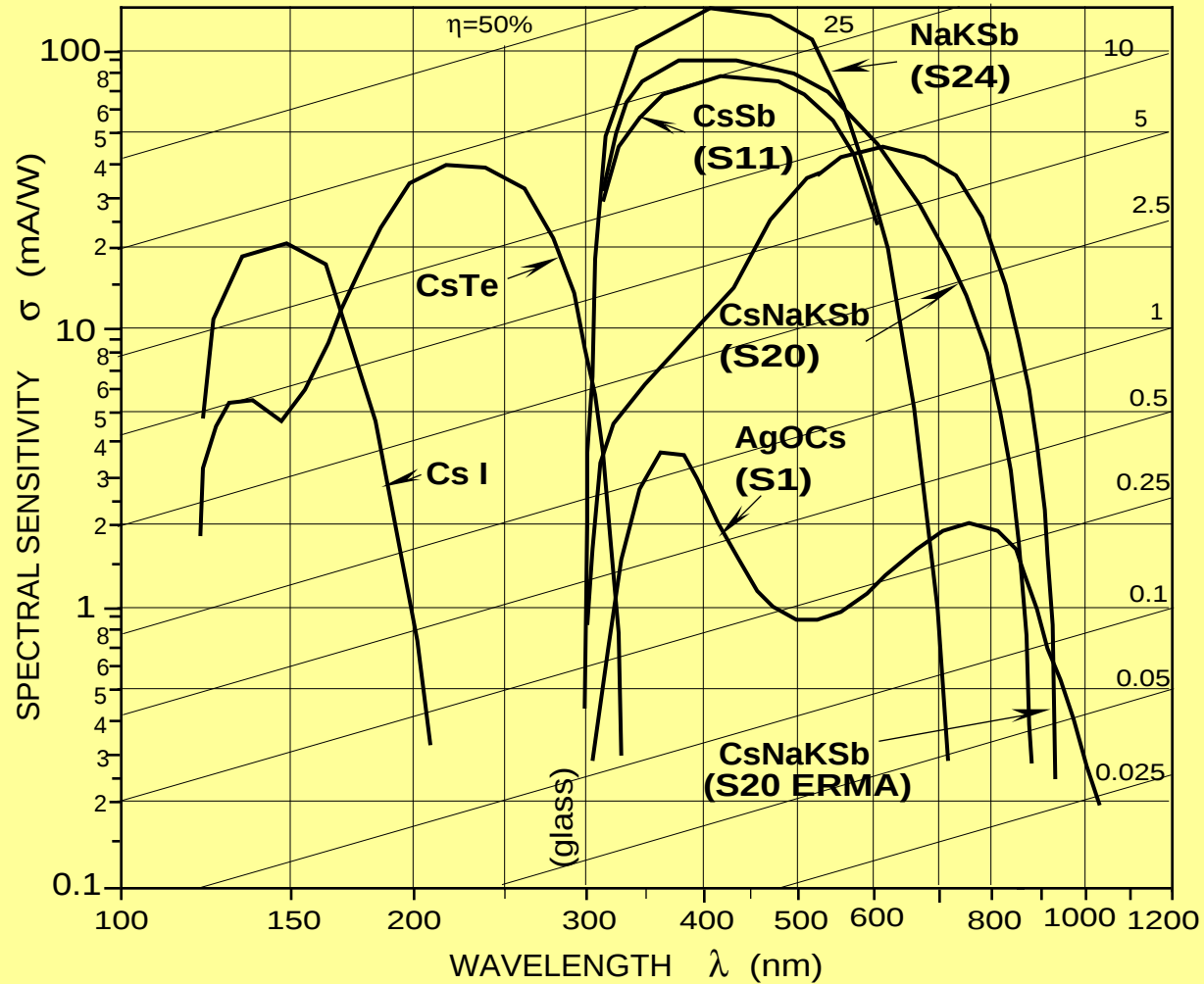


PHOTOCATHODE PARAMETERS

material	SD	E_g (eV)	E_A (eV)	E (eV)	E_p (eV)	λ_s (μm)	α (μm^{-1})	η_{max} (%)	J_{dark} (A/cm ²)
Na ₃ Sb		1.1	2.2	3.3	<4.3	.37	60	2	
K ₃ Sb		1.1	1.5	2.6	<3.7	.48	30	7	
Rb ₃ Sb		1.0	1.2	2.2	3.0	.57	30	10	
Cs ₃ Sb	S-11	1.6	0.45	2.05	2.0	.60	50	25	1 f
Na ₂ K Sb	S-24	1.0	1.0	2.0	3.0	.62	100	30	<0.1f
[Cs]Na ₂ K Sb	S-20	1.0	0.55	1.55	3.0	.80	100	35	1 f
Ag-O-Cs	S-1			≈ 1		1.2		1	1 p
Cs ₂ Te				3.7	5.0	.31		30	
GaAs [Cs ₂ O]		1.42	<0	1.4		.87		25	0.3 f
Ga _x In _{1-x} As [Cs]		1.1	<0	1.1		1.1		10	5 f
other semiconductors:									
Si		1.1	4.1	5.2	1.8			0.04	
Ge		0.7	4.5	5.2	1.5-2			0.08	

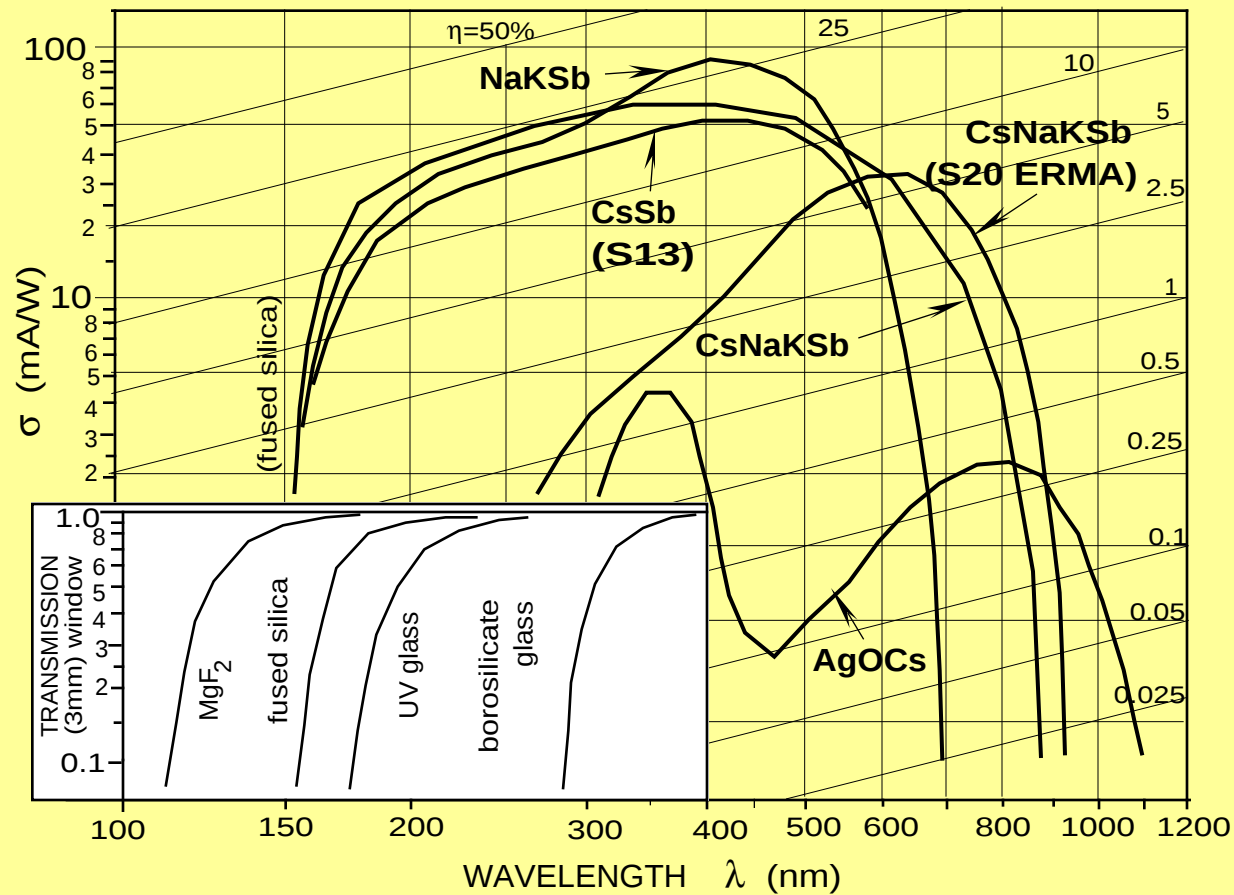
Notes: SD = standard international (EIA) designation of spectral response and window type;
 η_{max} = quantum peak efficiency (at $\lambda=\lambda_{\text{max}}$) for reflection photocathodes;
 α = optical absorption coefficient at $\lambda=\lambda_{\text{max}}$; J = dark current density,
in pico- or femto-ampere per cm² of photocathode surface (at 300 K).

TRANSMISSION PHOTOCATHODES



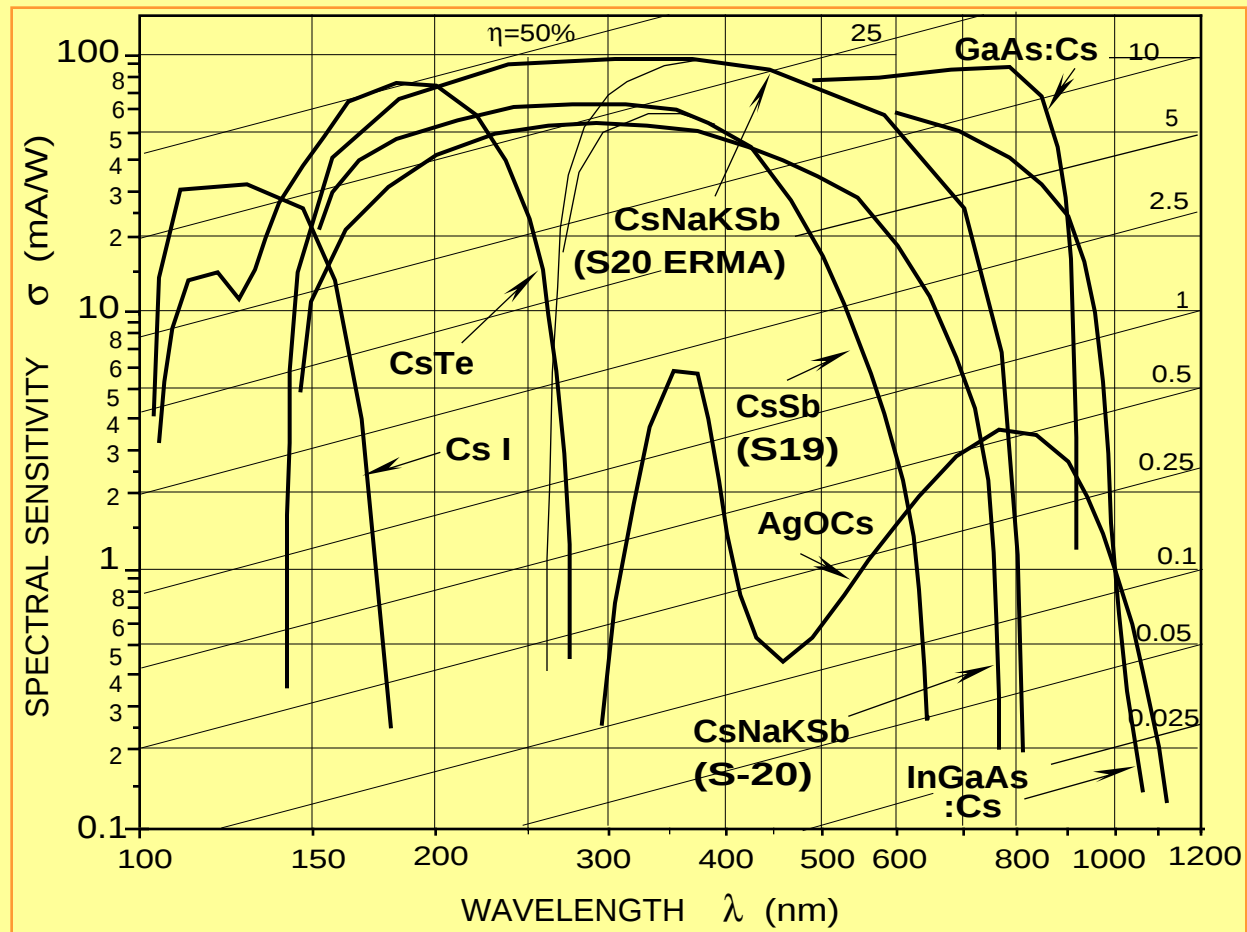
from: "Photodetectors", by S. Donati, Prentice Hall 2000

REFLECTION PHOTOCATHODES: UV-cutoff of a 3-mm thick window



from: "Photodetectors", by S. Donati, Prentice Hall 2000

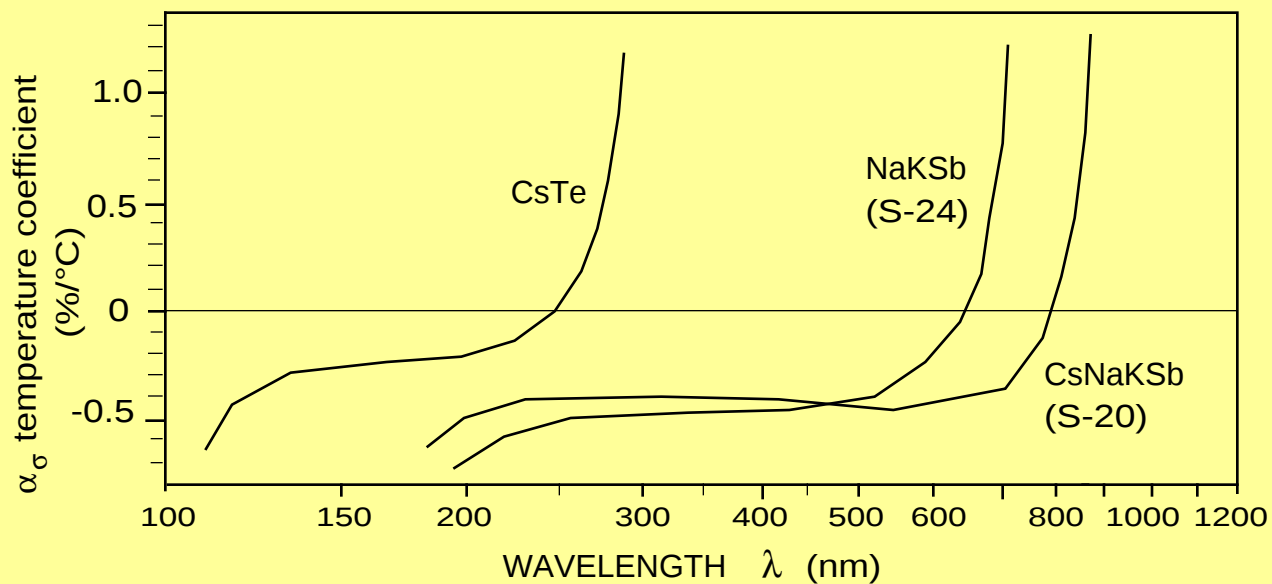
REFLECTION PHOTOCATHODES



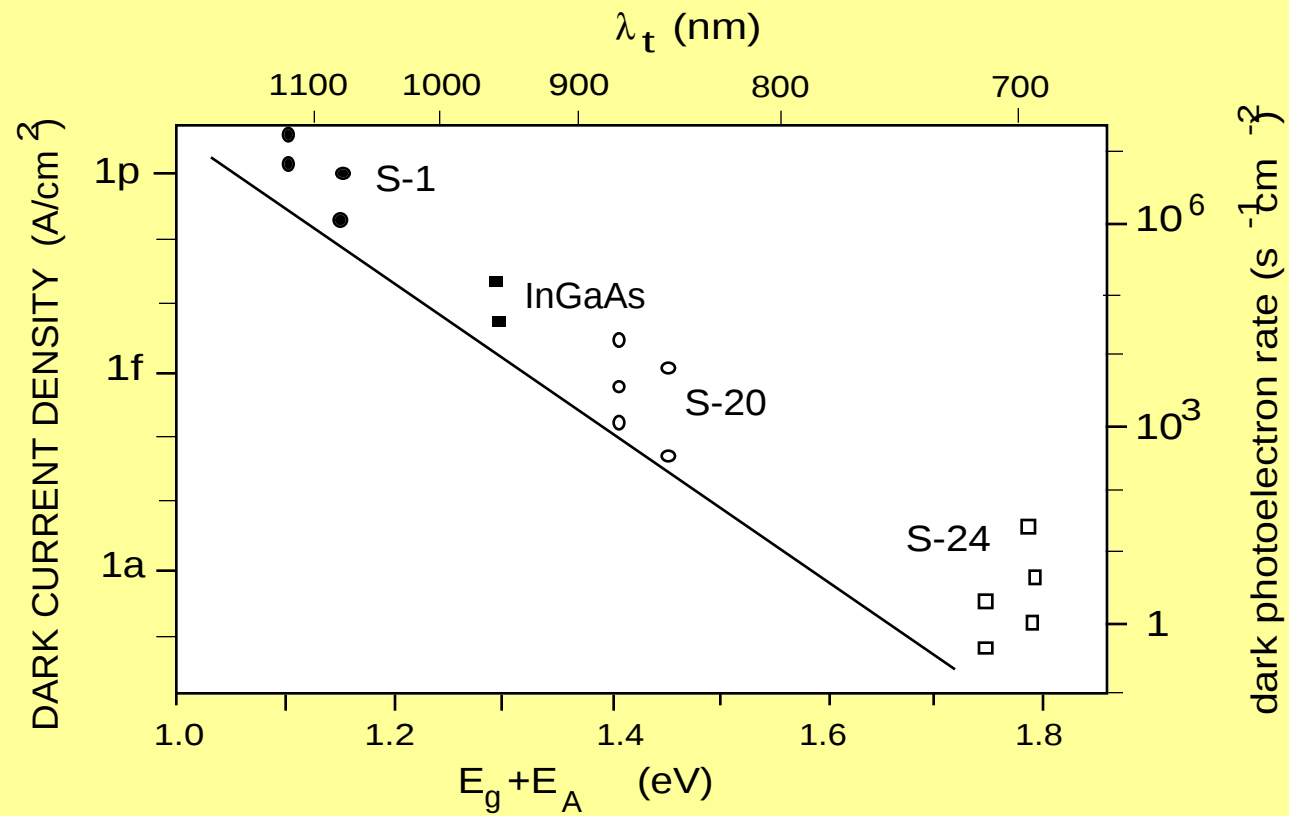
from: "Photodetectors", by S. Donati, Prentice Hall 2000

TEMPERATURE COEFFICIENT OF SPECTRAL SENSITIVITY

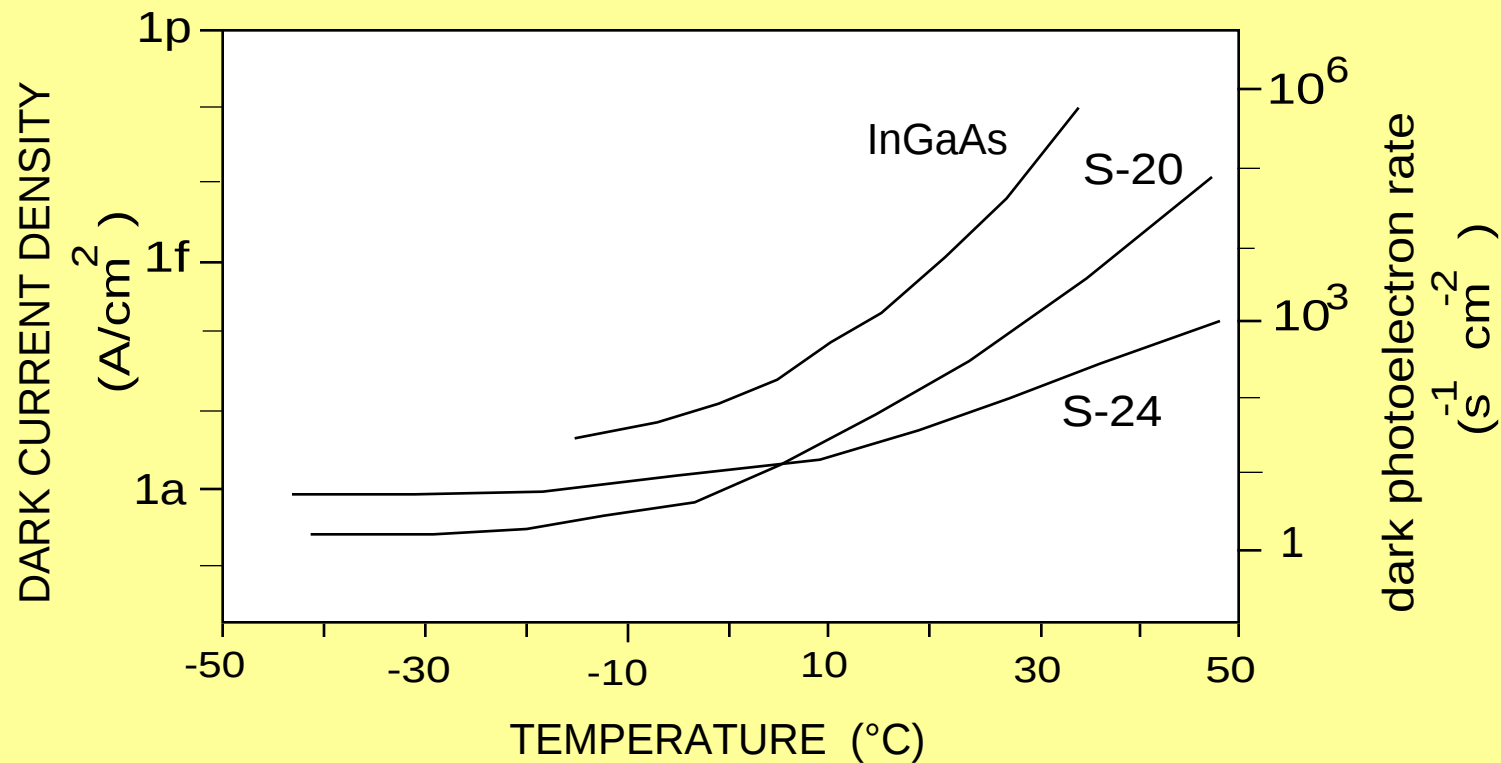
$$\alpha_{\sigma} = (1/\sigma) d\sigma/dT$$



DARK CURRENT vs WORKFUNCTION



DARK CURRENT TEMPERATURE COEFFICIENT



$$\alpha_J = (1/J_d) dJ_d/dT$$

$$= (2 + E_W/kT)/T \approx 0.34 (2 + E_W/kT) [\%/^{\circ}\text{C}]$$

PHOTOCATHODE FABRICATION

Common features:

- a high-vacuum process (10^{-6} torr)
- surface contaminants control very critical
- medium-temperature thin film deposition

Bi- and tri-alkaline fabrication:

- Sb evaporated first, (6 nm in transm. photocath),
- K in the stoichiometric ratio (K_3Sb) **
- then Na adding K and Sb in turn to have Na_2KSb **
- last Cs or Cs-O **

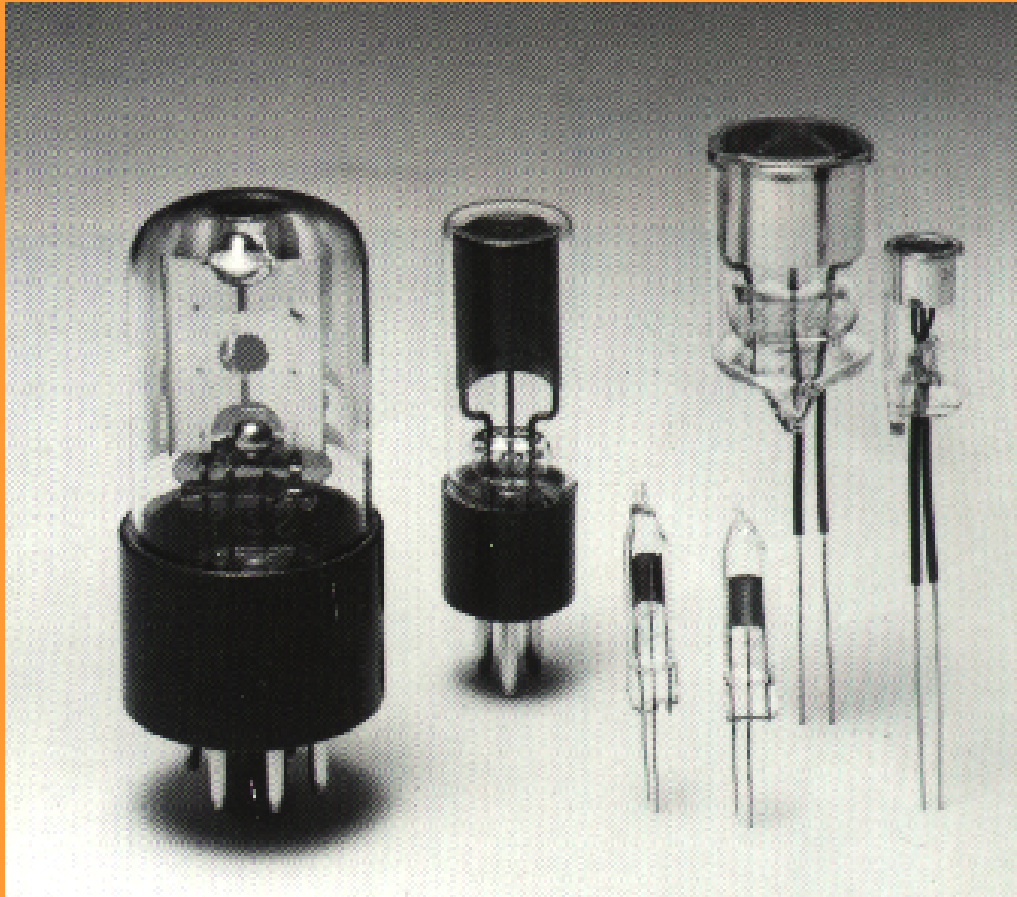
** = maximizing photoresponse

PHOTOCATHODE FABRICATION

Typical apparatus for photocathode fabrication

Picture
to be
added

PHOTOTUBES (or vacuum photodiodes)

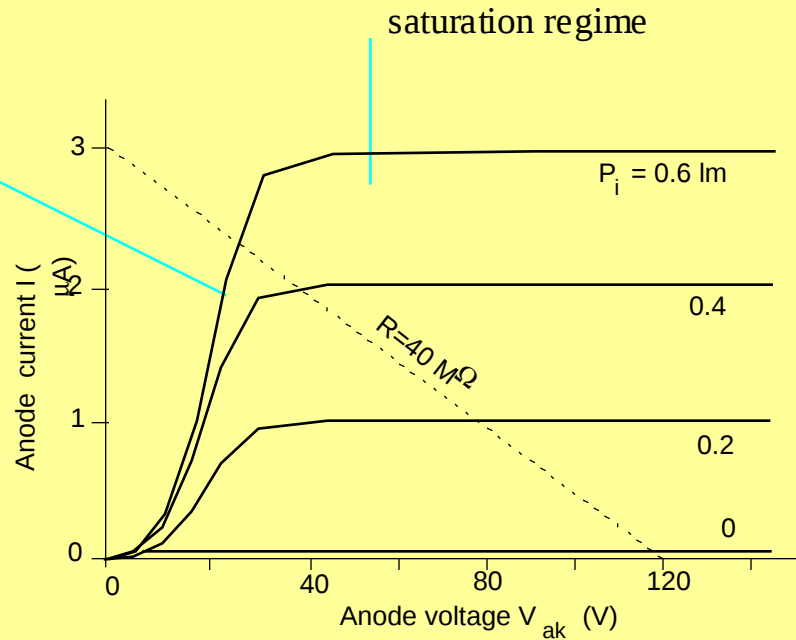


PT with hemicylindrical
reflection photocathode
(left) and with
transmission
photocathode on a plane
input window

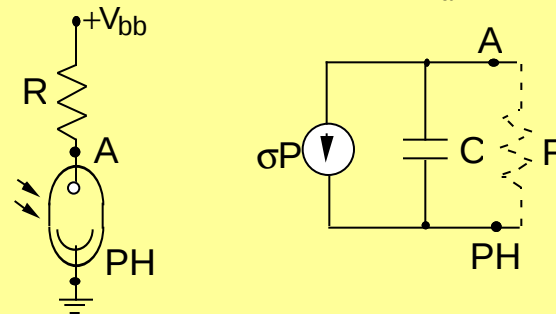
PHOTOTUBES

space charge regime
 $J_a = (4\epsilon_0/9d^2) (2e/m)^{1/2} V_{ak}^{3/2}$

V/I
 characteristics



bias and
 eqv circuit



PHOTOTUBES: speed of response

Transit time:

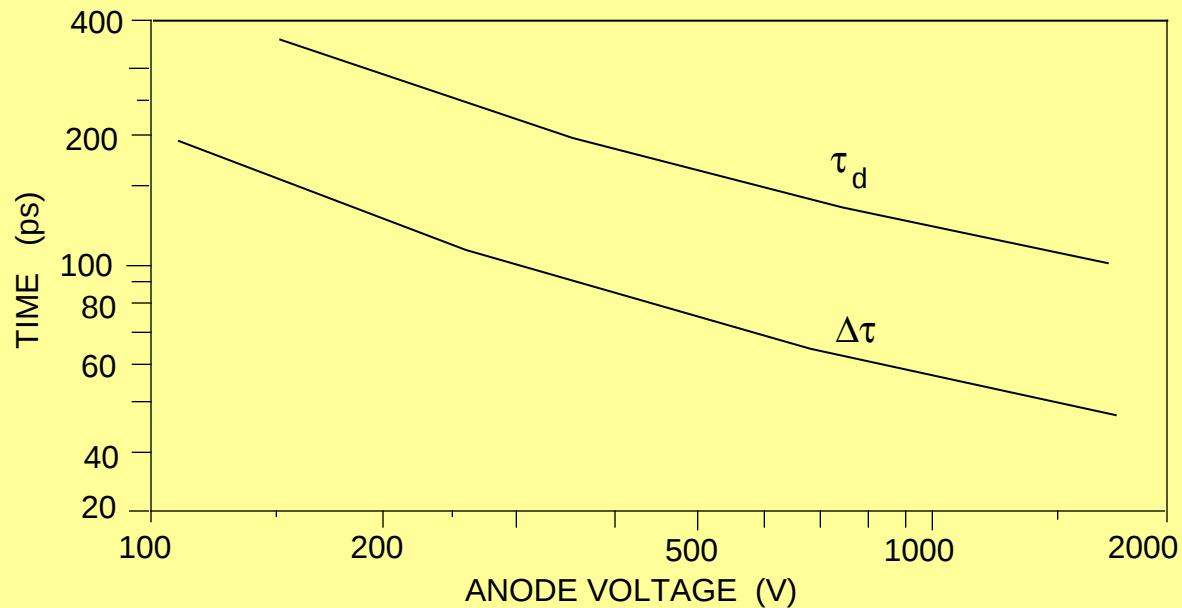
$$\tau_d = d (2m/eV_{ak})^{1/2} = 33.7 \text{ ns } d_{[\text{cm}]} (V_{ak})^{-1/2}$$

Dispersion: $\Delta\tau$ is a fraction of τ_d

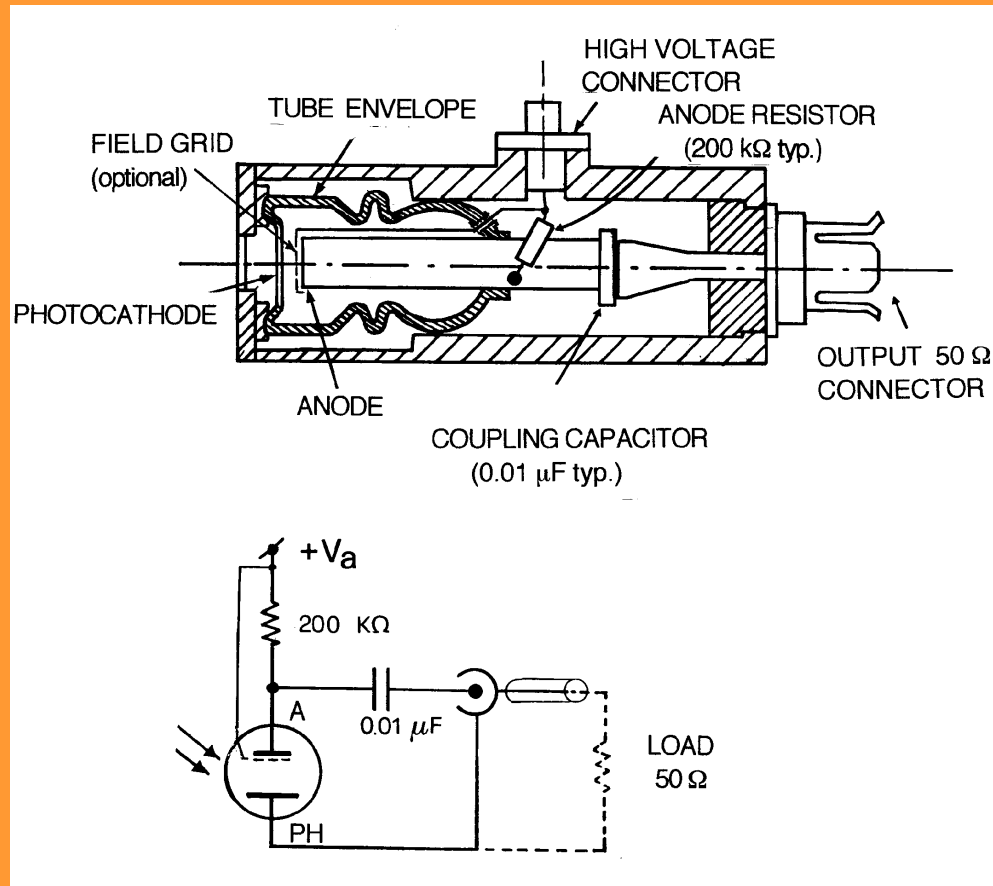
Frequency cutoff:

$$f_2 = 0.44/\Delta\tau \text{ (intrinsic cutoff), or}$$

$$f_2 = 1/2\pi RC_a \text{ (extrinsic cutoff)}$$



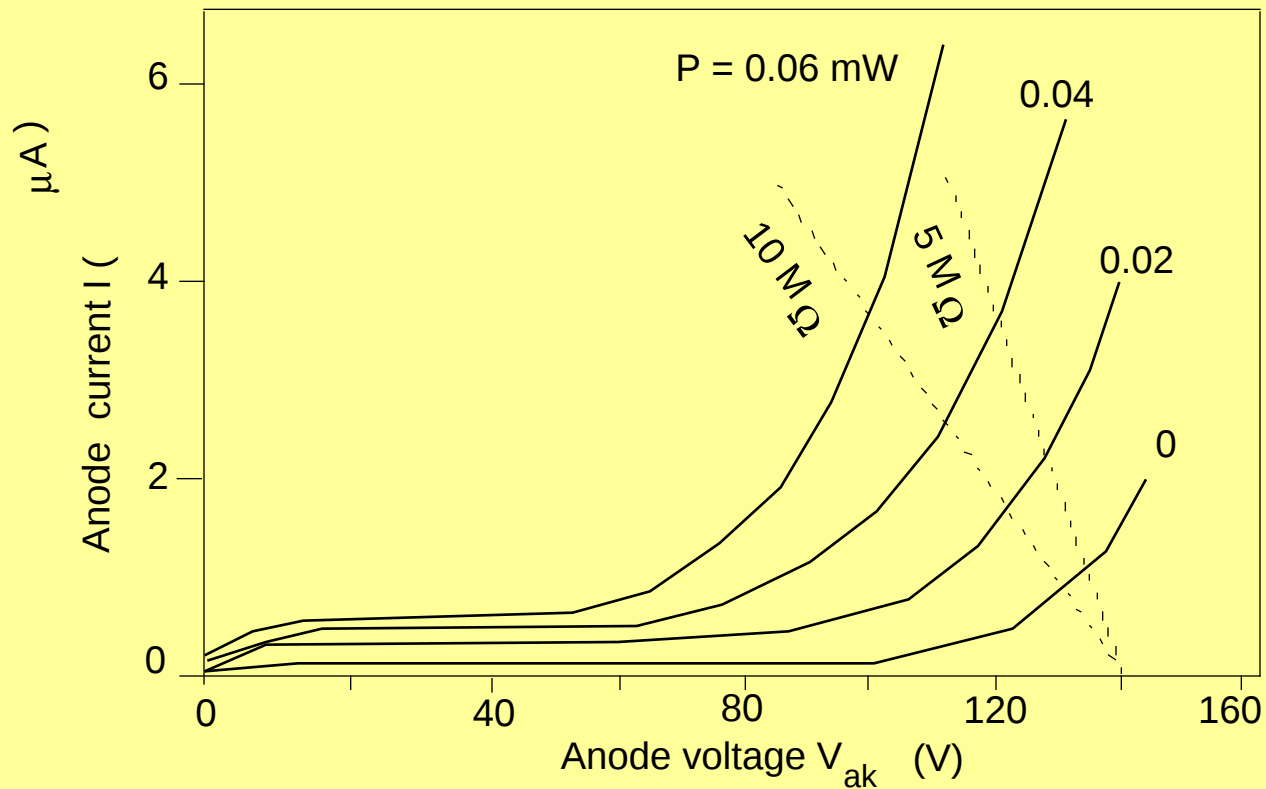
TYPICAL FAST PHOTOTUBE



A fast phototube (rise time 100 ps or bandwidth 3 GHz) with transmission photocathode (S-1, S-11 or S-20) on a glass or quartz window and 50-Ohm output electrode. Top: device structure; bottom: bias circuit. With the field grid, speed of response is limited by the dispersion Δt rather than by the transit time τ_d

GAS PHOTOTUBE

Ionization in a low-pressure gas filling the tube is a mechanism to increase photoelectron number. Internal gain is typically $G=5-20$



Gas phototubes are used in industrial flame control